

Substitute for Form 1449 A &amp; B/PTO

**INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Complete if Known

10/549901

Sheet 1 of 1				Application Number	Based on PCT/JP2004/003617
				Confirmation Number	Unknown
				Filing Date	September 20, 2005
				First Named Inventor	Hiroyuki AKAGAWA
				Art Unit	Unknown
				Examiner Name	Unknown
				Attorney Docket Number	Q90414

**U.S. PATENT DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		Number	Kind Code <sup>2</sup> (if known)		
		US			
		US			
		US			
		US			
		US			
		US			
		US			
		US			
		US			

**FOREIGN PATENT DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document			Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Translation <sup>6</sup>
		Country Code <sup>3</sup>	Number <sup>4</sup>	Kind Code <sup>5</sup> (if known)			
/S.F./		JP	2003-51472	A	02-21-2003	SHINETSU CHEMICAL CO	Abstract
		JP	2002-162726	A	06-07-2002	HOYA CORP.	Abstract
		JP	2004-54285	A	02-19-2004	HOYA CORP.	Abstract
		JP	2004-29735	A	01-29-2004	HOYA CORP.	Abstract
		JP	64-40267	A	02-10-1989	SHINETSU CHEMICAL CO., NAOETSU SEIMITSU KAKO KK	Abstract
		JP	2002-318450	A	10-31-2002	SHINETSU CHEMICAL CO	Abstract

**NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	Translation <sup>6</sup>
/S.F./		MASAMITSU ITOH, et al., New Concept of Specification for Mask Flatness, Proceedings of SPIE Photomask and Next-Generation Lithography Mask Technology IX, SPIE Vol. 4754 (2002), 43-53	

Examiner Signature	/Stewart Fraser/	Date Considered	09/23/2008
--------------------	------------------	-----------------	------------

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup>Applicant's unique citation designation number (optional). <sup>2</sup>See Kind Codes of USPTO Patent Documents at [www.uspto.gov](http://www.uspto.gov), MPEP 901.04 or in the comment box of this document. <sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard ST. 3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup>Applicant is to indicate here if English language Translation is attached.